IN THE SPECIFICATION:

Please amend the paragraph on page 8, lines 13-22 of the Specification as follows:

A catalyst layer having a thickness of 5, 10, 20, 25 or 50 nm was formed on the surface of a glass substrate according to the sputtering method using Inver-42 INVAR 42 as a catalyst. Each of these substrates provided thereon with such a catalyst layer was introduced into a thermal CVD equipment and then the equipment was evacuated to a pressure of 1 Pa. Thereafter, a process gas comprising 50/50 (% by volume) mixture of CO and H₂ gases was introduced into the equipment up to the atmospheric pressure. The substrate was heated up to 550°C and the raw gases were reacted for 15 minutes while maintaining the system at that temperature to thus form a graphite nanofiber (GNF) having a diameter of about 50 nm and a length of 1 μm.

Please amend the paragraph on page 9, lines 7-15 of the Specification as follows:

Fig. 1 is an SEM cross sectional micrograph of a sample having a thin catalyst layer on the order of 10 nm and Fig. 2 is an SEM cross sectional micrograph of a sample having a thick catalyst layer on the order of 50 nm, among the samples listed in Table 1. The results shown in these figures Figures 1 and 2 clearly indicate that when the catalyst layer is thin (Fig. 1), any a non-fibrous layer is not observed formed and that when the catalyst layer is thick (Fig. 2), there is observed the formation of a catalyst non-fibrous layer in having a thickness of about 1 μm. The results listed in Table 1 and

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depicted on Figs. 1 and 2 clearly indicate that when the catalyst layer is thin, the non-fibrous layer formed is also thin.

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